

**Amendments to the Claims**

Claims 1-54 (Cancelled).

55. (Previously presented) A sputtering target formed from a cast material and comprising:  
a yield strength of greater than 50 mega Pascal (MP), and an ultimate tensile strength of greater than 125 MP;  
a substantial absence of pores, voids and inclusions; and  
an average grain size of less than about 1  $\mu\text{m}$ , the target having an annealed upper surface portion and a remaining portion that is un-annealed.

56. (Previously presented) The sputtering target of claim 55 comprising one or more of Al, Ti, Cu, Ta, Ni, Mo, Au, Ag, and Pt.

57. (Previously presented) The sputtering target of claim 55 comprising an alloy which includes at least one of Al, Ti, Cu, Ta, Ni, Mo, Au, Ag and Pt.

58. (Previously presented) The sputtering target of claim 55 further comprising a substantial absence of precipitates.

59. (Previously presented) The sputtering target of claim 55 further comprising a substantially uniform structure and texture at any location.

60. (Previously presented) The sputtering target of claim 55 further comprising a substantially homogeneous composition at any location.

Claims 61-72. (Cancelled)

73. (Previously presented) The sputtering target of claim 55 wherein both the yield strength and the ultimate tensile strength are greater than 125 MP.

74. (Previously presented) The sputtering target of claim 55 wherein both the yield strength and the ultimate tensile strength are greater than 150 MP.